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Form PTO-1449 U.S. Department of Commerce
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Att. Docket No.

Serial No.

NOV 30 2001
FSI0022/0301

09/923,188

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Applicant

Sloan et al.


Filing Date

Group

August 6, 2001

3743


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Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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